Introduction of New Products

**Field Emission Electron Microscope**

**JEM-2100F**

The field-emission electron gun (FEG), which provides an electron beam with high brightness and high coherence, is essential for high-resolution observation and nano-area analysis. The JEM-2100F, featuring advanced digital operation, is an integrated TEM that gives full play to its various functions.

- Point resolution: 0.19 nm
- Accelerating voltage: 160, 200 kV
- Magnification: 50 to 1,500,000

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**Scanning Electron Microscope**

**JSM-6060LV / JSM-6060**

JSM-6060 is the high performance general purpose SEM with the optics and the operation software basically same as the one developed for JSM-6460. JSM-6060 is packaged in a small console to allow more freedom in layout. The completely automated electron gun and the JEOL unique zoom condenser lens, which allow optimization of the optics quickly, make the operation comfortable. Also, a low vacuum (LV) version JSM-6460LV and an analytical SEM version JSM-6460A/JSM-6460LA are available.

- Resolution: 3.5 nm (LV: 4.0 nm)
- Accelerating voltage: 0.5 to 30 kV
- Magnification: 5 to 300,000

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**Electron Beam Lithography System**

**JBX-3030MV**

The JBX-3000MV is an electron beam lithography system for mask/reticle fabrication that meets the design rule of 100 to 70 nm. This system features pattern writing with high speed, high accuracy and high reliability, achieved by high-end technology.

- Accelerating voltage: 50 kV
- Electron gun emitter: LaB6 single crystal
- Workpiece dimension: up to 178 mm square
- Field stitching accuracy: ±9 nm
- Overlay accuracy: ±12 nm